

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	26	(Ouellet.in. or Grondin.in. or Lachance.in. or Blain.in. or (Dalsa adj semiconductor).as.) and ((PECVD or plasma or PCVD or (P-CVD)) with (silica or SiO2 or "SiO.sub.2" or SiO or SiOx or "SiO.sub.x" or (silicon adj \$2oxide)))	US-PGPUB; USPAT	OR	ON	2005/12/20 12:01
L3	9	(Ouellet or Grondin or Lachance or Blain or (Dalsa adj semiconductor)) and ((PECVD or plasma or PCVD or (P-CVD)) same (silica or SiO2 or "SiO.sub.2" or SiO or SiOx or "SiO.sub.x" or (silicon adj \$2oxide)))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:02
L4	1713	(427/569,574).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/12/20 12:02
L5	508	(427/579).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/12/20 12:02
L6	387	(427/255.37).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/12/20 12:02
L7	3772	((427/163.2,167) or (385/129,130,131,132)).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/12/20 12:02
L8	3107	(427/372.2,397.7).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2005/12/20 12:02
L9	8668	L4 L5 L6 L7 L8	US-PGPUB; USPAT	OR	ON	2005/12/20 12:02
L10	2	L5 and L7 and L8	US-PGPUB; USPAT	OR	ON	2005/12/20 12:02
L11	14	L5 and L8	US-PGPUB; USPAT	OR	ON	2005/12/20 12:02
L12	16	L5 and L7	US-PGPUB; USPAT	OR	ON	2005/12/20 12:03
L13	123	L5 and ((control\$4 or regulat\$3 or monitor\$3) near3 pressure)	US-PGPUB; USPAT	OR	ON	2005/12/20 12:04
L14	115	L5 and ((silane or monosilane or SiH4 or "SiH.sub.4") same (N2O or "N.sub.2O" or "N.sub.2 O" or (nitrous adj oxide)) same (N2 or "N.sub.2" or nitrogen))	US-PGPUB; USPAT	OR	ON	2005/12/20 12:04
L15	8668	L4 L5 L6 L7 L8	US-PGPUB; USPAT	OR	ON	2005/12/20 12:04

L16	44	L15 and ((silane or monosilane or SiH4 or "SiH.sub.4") same (N2O or "N.sub.2O" or "N.sub.2 O" or (nitrous adj oxide)) same (N2 or "N.sub.2" or nitrogen)) and ((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x")) and (multiplex\$4 or demultiplex\$4 or Mux or Dmux or waveguide or lightguide or (wave adj guide) or (light adj guide))	US-PGPUB; USPAT	OR	ON	2005/12/20 12:05
L18	201	((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x")) and (waveguide or (wave adj guide) or lightguide or (light adj guide) or Dmux or mux or multiplex\$3 or demultiplex\$3) and ((control\$4 or regulat\$4 or optimiz\$5) near4 pressure) and ((anneal\$3 or heat\$3 or bake or baked or baking or temperature) near5 (reduc\$5 or minimiz\$5 or eliminat\$4 or contamin\$5 or unwanted or expel\$4 or compound))	US-PGPUB; USPAT	OR	ON	2005/12/20 12:05
L19	199	((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x")) and ((optimiz\$9 or different or chang\$4 or alter\$5 or vary\$4 or varied or variable) near3 pressure) and ((set\$5 or fix\$5 or predetermin\$5 or (pre adj determin\$5)) near4 (flow adj rate))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:07
L20	32	L19 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:36
L22	26	L19 and ((test\$5 or monitor\$5 or observ\$8) near3 (optical or absorb\$9 or peak or transmit\$9))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:09
L23	32	L19 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:10

L24	26	L19 and ((test\$5 or monitor\$5 or observ\$8) near3 (optical or absorb\$9 or peak or transmit\$9))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:10
L25	145	L19 not (L23 or L24)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:10
L26	60	((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x")) same ((optimiz\$9 or different or chang\$4 or alter\$5 or vary\$4 or varied or variable) near3 pressure)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:12
L27	11	L26 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:12
L28	11	L26 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:12
L29	49	L26 not L28	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:12
L30	8668	L4 L5 L6 L7 L8	US-PGPUB; USPAT	OR	ON	2005/12/20 12:12
L31	324	L30 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:13
L32	41	((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x" or silicate or glass or BPSG or PSG or FSG)) and (((optimiz\$9 or different or chang\$4 or alter\$5 or vary\$4 or varied or variable) near3 pressure) same ((fix\$5 or constant or predetermin\$5 or (pre adj determin\$7) or set) near3 (flow adj rate)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:14

L33	41	((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x" or silicate or glass or BPSG or PSG or FSG)) and (((optimiz\$9 or different or chang\$4 or alter\$5 or vary\$4 or varied or variable) near3 pressure) same ((fix\$5 or constant or predetermin\$5 or (pre adj determin\$7) or set) near3 (flow adj rate))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:15
L34	7	L33 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:15
L35	7	L33 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:16
L36	307	((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x" or silicate or glass or BPSG or PSG or FSG)) and (((optimiz\$9 or different or chang\$4 or alter\$5 or vary\$4 or varied or variable) near3 pressure) and ((fix\$5 or constant or predetermin\$5 or (pre adj determin\$7) or set) near3 (flow adj rate))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:16
L37	50	L36 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:16
L38	43	L37 not L35	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:16
L39	257	L36 not L37	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:17

L40	56	((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x" or silicate or glass or BPSG or PSG or FSG)) and (((optimiz\$9 or different or chang\$4 or alter\$5 or vary\$4 or varied or variable) near3 pressure with ("2" or "2.0" or "2.1" or "2.2" or "2.3" or "2.4" or "2.5" or "2.6") near3 torr))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:20
L41	2	L40 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:20
L42	2	L40 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:20
L43	54	L40 not L42	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:21
L45	79	((plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x" or silicate or glass or BPSG or PSG or FSG)) same (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:21
L46	10	((pacvd or plasma or PECVD or PCVD or P-CVD) with ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x" or silicate or glass or BPSG or PSG or FSG)) and ((silicon or silane or monosilane or SiH4 or "SiH.sub.4") with ("200" or "0.2" or "0.20")) and ((oxygen or O2 or "O.sub.2" or oxidation or N2O or "N.sub.2O" or "N.sub.2 O" or ((nitrous or nitric) adj oxide)) with ("6" or "6.0" or "6000")) and ((carrier or N2 or nitrogen or "N.sub.2" or Ar or argon or Kr or krypton or xe or xenon or inert or noble) with ("3.15" or "3150"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:27

L47	15	((pacvd or plasma or PECVD or PCVD or P-CVD) same ((silicon adj \$2oxide) or silica or SiO2 or "SiO.sub.2" or SiOx or SiO or "SiO.sub.x" or silicate or glass or BPSG or PSG or FSG)) and ((silicon or silane or monosilane or SiH4 or "SiH.sub.4") with ("200" or "0.2" or "0.20" or "0.200" or ".2" or ".200" or ".20")) and ((oxygen or O2 or "O.sub.2" or oxidation or N2O or "N.sub.2O" or "N.sub.2 O" or ((nitrous or nitric) adj oxide)) with ("6" or "6.0" or "6000" or "6.00")) and ((carrier or N2 or nitrogen or "N.sub.2" or Ar or argon or Kr or krypton or xe or xenon or inert or noble) with ("3.15" or "3150"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:54
L48	6	L47 and (FTIR or (fourier adj transform\$6) or (FT adj IR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:36
L49	10	L47 and (anneal\$5 or bake or baked or baking or rta or rtp)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/20 12:37